

TEMPO: Time resolved Experiments on Materials with Photoelectron spectroscopy

SOLEIL staff:

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Areas of application, instrumentation and methodologies used

Energy range: 50 – 1500 eV

Time-resolved spectroscopy for magnetism and physical chemistry.

Ultraviolet photoemission spectroscopy (UPS) of valence bands.

Time-resolved photoemission and photo-absorption studies in the soft x-ray range.

Branch A: UHV photoemission - VG SCIENTA spectrometer - 2D detector.

Magnetism - conventional semiconductor and multilayer crystals (graphene, graphite, MoS etc.) samples. Cryostat between 25 K and 400 K or 50 K and 1,200 K for magnetism and semiconductor environments - Argon ion bombardment - furnace for annealing at 2000 °C.

High-repetition-rate pulsed femtosecond laser (Coherent REGA 9040). Synchronization with synchrotron radiation

Branch B: for the use of equipment from outside laboratories:

Near Ambient Pressure Photoemission: (NAP-XPS) (LCP-MR, Paris VI), F. Rochet, J.J.Gallet. XPEEM, L. Néel (Jan Vogel)- NanoEsca, LETI, (O. Renault) - Coherent scattering- gas phase coincidence, LCPMR (F. Penent).

Major disciplines

Surfaces and interfaces, magnetization dynamics - surface reactivity of oxides and semiconductors- 2D-materials and solar cells. Laser+RS for magnetization and excited electronic states.

Temporal changes in the chemical environment of surfaces – catalysis and new materials.

Magnetism: XMCD / Magnetization dynamics in the picosecond and sub-picosecond time scales

Surface science: Chemical analysis and imaging of thin films/ Kinetics of surface alloy formation in real time, semiconductor physics.

Chemistry: Laser-induced photochemistry (ps and sub ps)/ Reaction kinetics/ catalysis

Applied research: analysis and expertise in surface science and time-dependent applications.